

ABSTRACT

**Process for fabricating a microstructure containing a
vacuum cavity, and microstructure**

The invention relates to a process for fabricating a microstructure containing a vacuum cavity. It comprises the following steps that consist in:

a) producing, from a first silicon wafer, a porous silicon region intended to form, completely or partly, one wall of the cavity and capable of absorbing residual gases in the cavity;

b) joining the first silicon wafer to a second wafer, so as to produce the cavity.

No figure